

Electronic Supplementary Material (ESI) for New Journal of Chemistry.

Supplementary data to
Tunable electronic properties and band alignments of InS-arsenene
heterostructure via external strain and electric field

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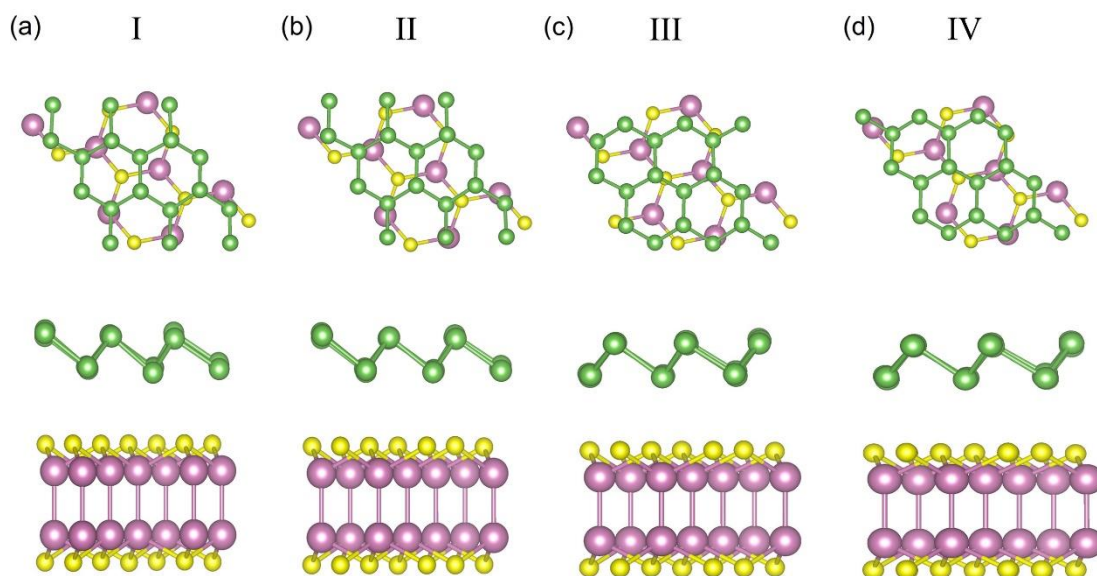
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Supplementary Figures

Figure S1.(color online) Top and side views of InS-Arsenene vdWH with different stacking patterns. (a) The first As atom of upper arsenene layer align with S atom, (b) The first As atom of upper arsenene layer align with In atom, (c) The first As atom of lower arsenene layer align with S atom, (d) The first As atom of lower arsenene layer align with In atom. The I stacking pattern has the lowest binding energy.



| Stacking patterns | I | II | III | IV |
|------------------------|--------|--------|--------|-------|
| Binding Energy (meV/Å) | -113.2 | -112.4 | -111.9 | 111.3 |

Figure S2.(color online) The left column : elastic modulus C_{2D} , and right column: deformation potential constant E_{DP} at different directions for isolated InS monolayer, arsenene monolayer and InS-arsenene vdWH.

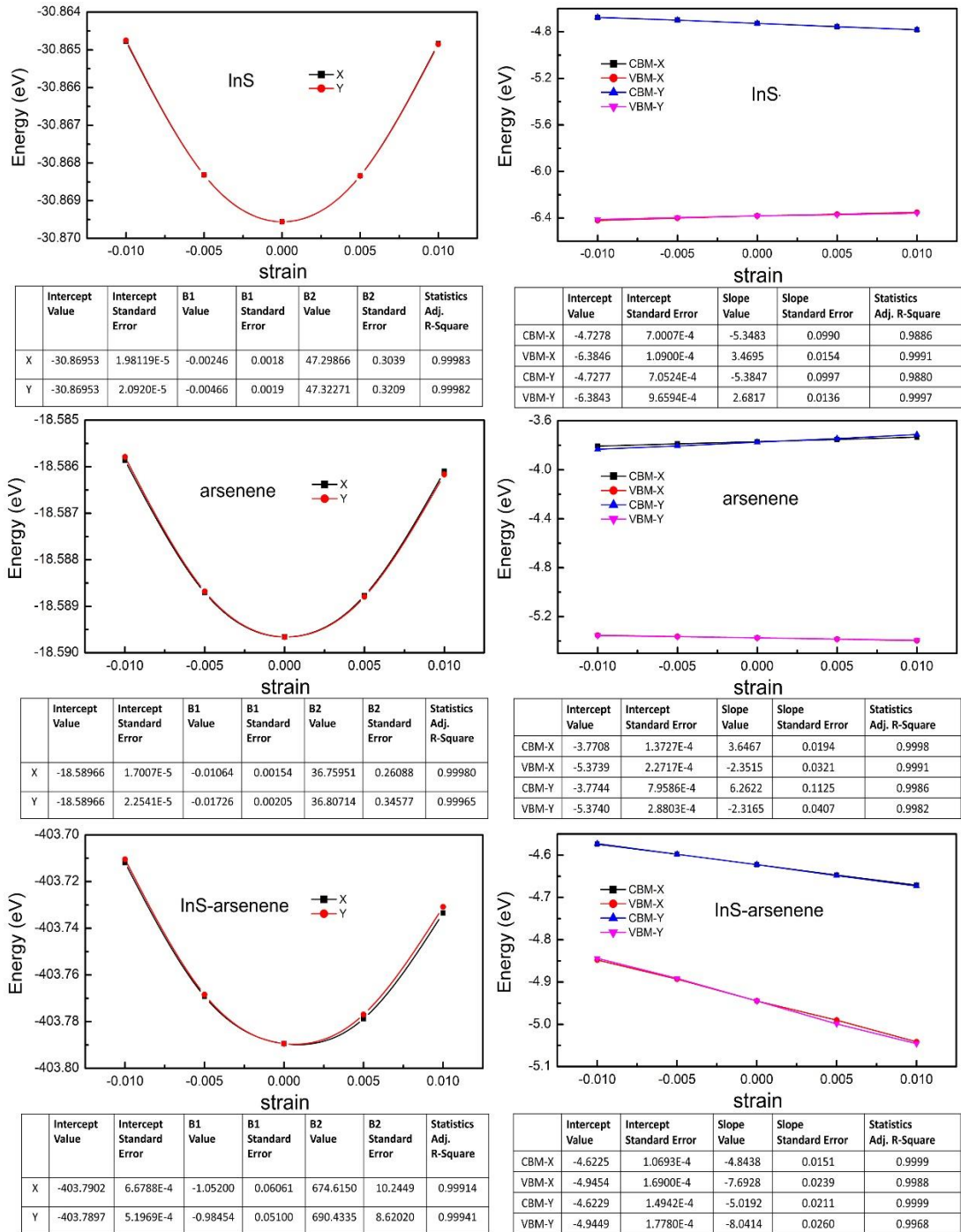


Figure S3.(color online) The band structures of (a) InS monolayer, (b) arsenene(As) monolayer and (c) InS-As vdWH at HSE level. In each panel, the Fermi level is set to zero.

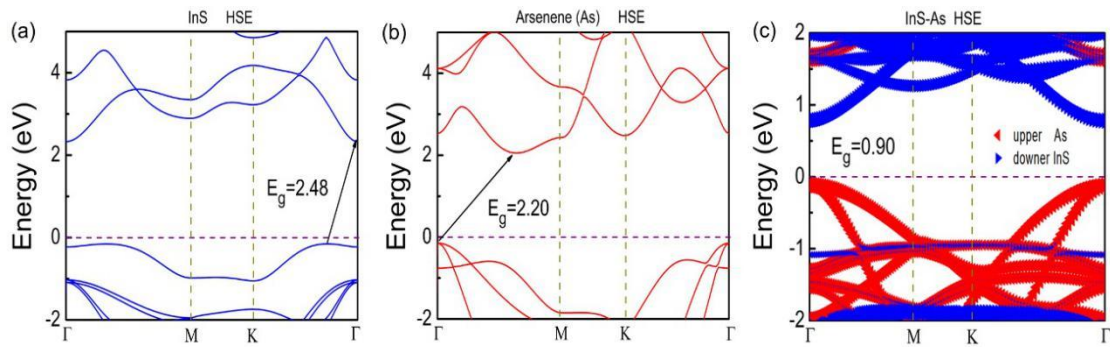


Figure S4. (color online) The projected band structures of InS-As vdWH under finite vertical strains (a) $\Delta d = -0.8 \text{ \AA}$, (b) $\Delta d = 0.4 \text{ \AA}$ and (c) $\Delta d = 1.8 \text{ \AA}$ at HSE level. In each panel, the Fermi level is set to zero.

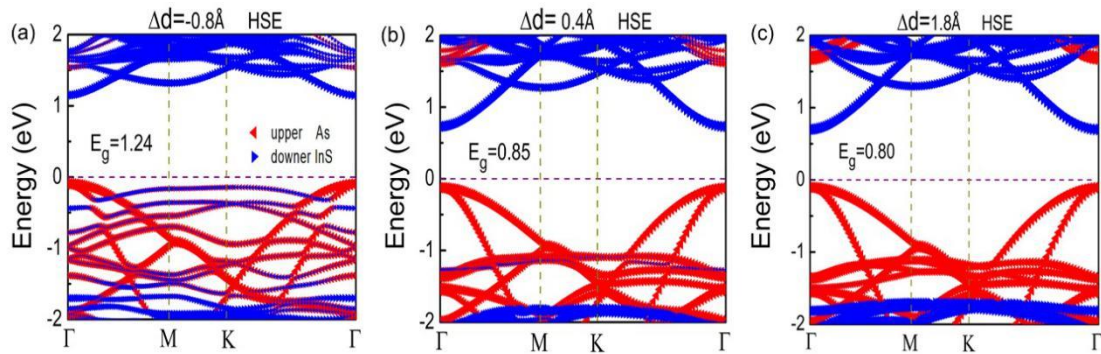


Figure S5. (color online) The projected band structures of InS-As vdWH under finite in-plane strains (a) $\varepsilon = -8\%$, (b) $\varepsilon = 2\%$ and (c) $\varepsilon = 4\%$ at HSE level. In each panel, the Fermi level is set to zero.

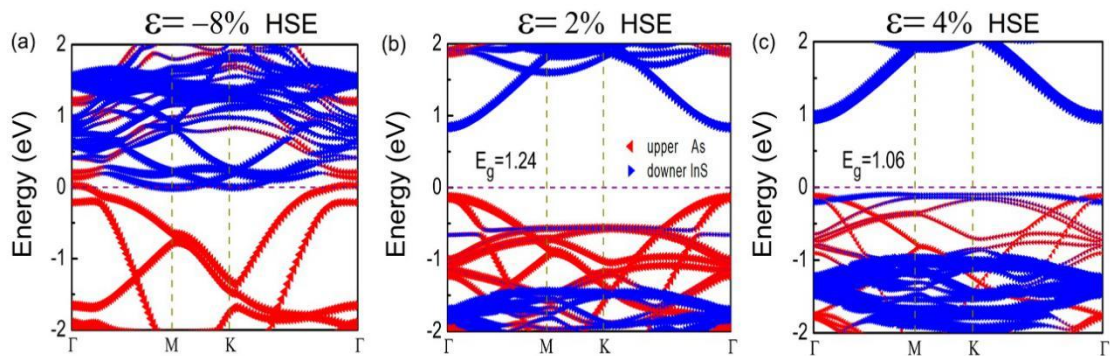


Figure S6. (color online) The projected band structures of InS-As vdWH under finite electric fields (a) $E_{ext} = -0.5 \text{ V/\AA}$, (b) $E_{ext} = 0.6 \text{ V/\AA}$ and (c) $E_{ext} = 0.8 \text{ V/\AA}$ at PBE level and (d) $E_{ext} = -0.8 \text{ V/\AA}$, (e) $E_{ext} = 0.6 \text{ V/\AA}$ and (f) $E_{ext} = 0.8 \text{ V/\AA}$ at HSE level. In each panel, the Fermi level is set to zero.

